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(12) **United States Design Patent**
Zhu

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(54) **FACE MASK**

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(**) Term: **15 Years**

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(51) **LOC (13) Cl.** **29-02**

(52) **U.S. Cl.**
USPC **D29/108**; D24/110.1

(58) **Field of Classification Search**
USPC D2/866; D24/110.1, 110.2, 127; D29/105, 107, 108, 110, 129
CPC A41D 13/11; A41D 13/1107; A41D 13/1161; A42B 3/225
See application file for complete search history.

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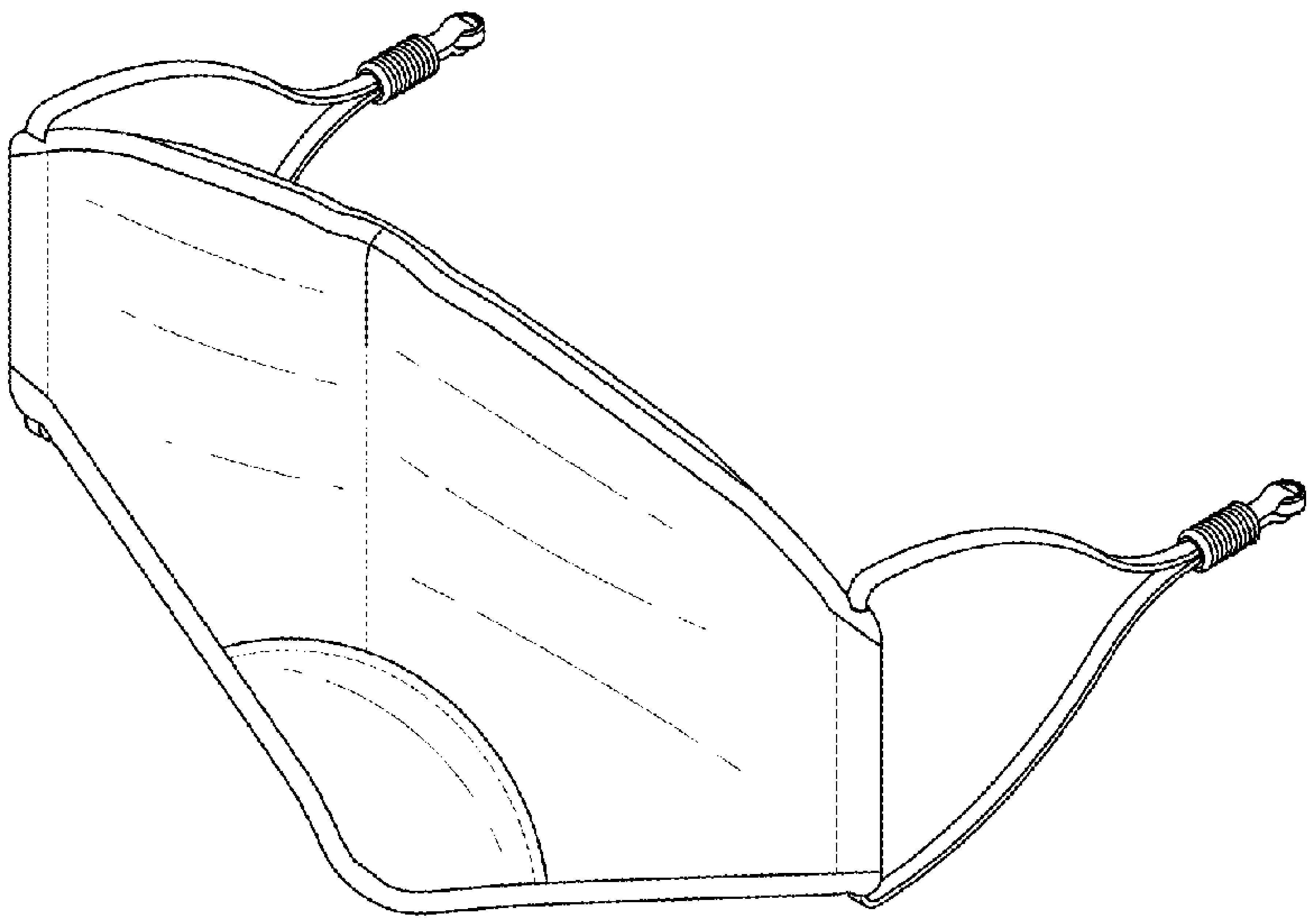
(57) **CLAIM**

What is claimed is an ornamental design for a face mask, as shown.

DESCRIPTION

FIG. **1** is a perspective view of a face mask showing our new design;
FIG. **2** is a frontal elevational view thereof;
FIG. **3** is a rear elevational view thereof;
FIG. **4** is a top view thereof;
FIG. **5** is a bottom view thereof; and,
FIG. **6** is a side elevational view thereof.
The broken lines in the figures illustrate portion of the face mask that form no part of the claimed design.

1 Claim, 6 Drawing Sheets



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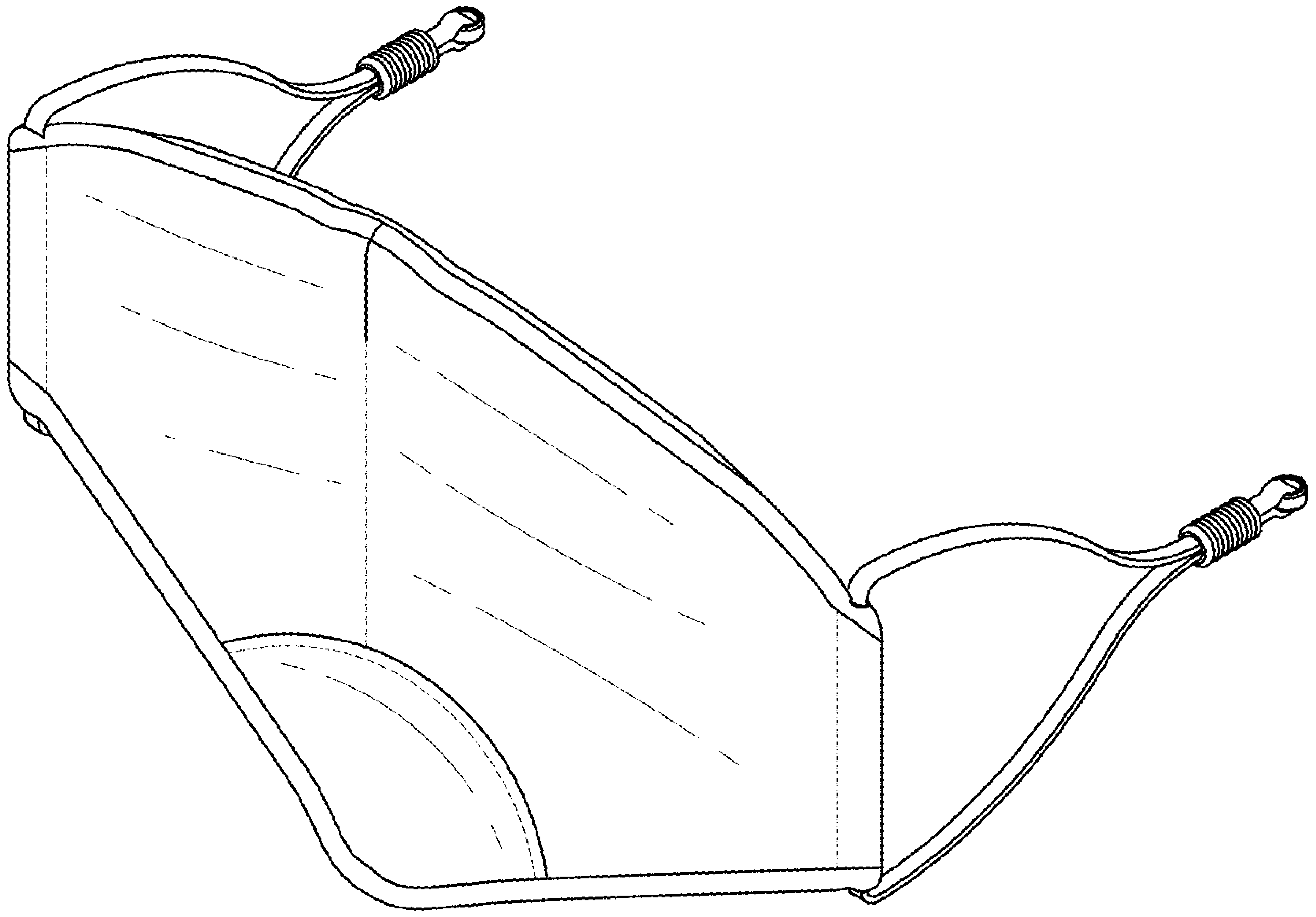

FIG. 1

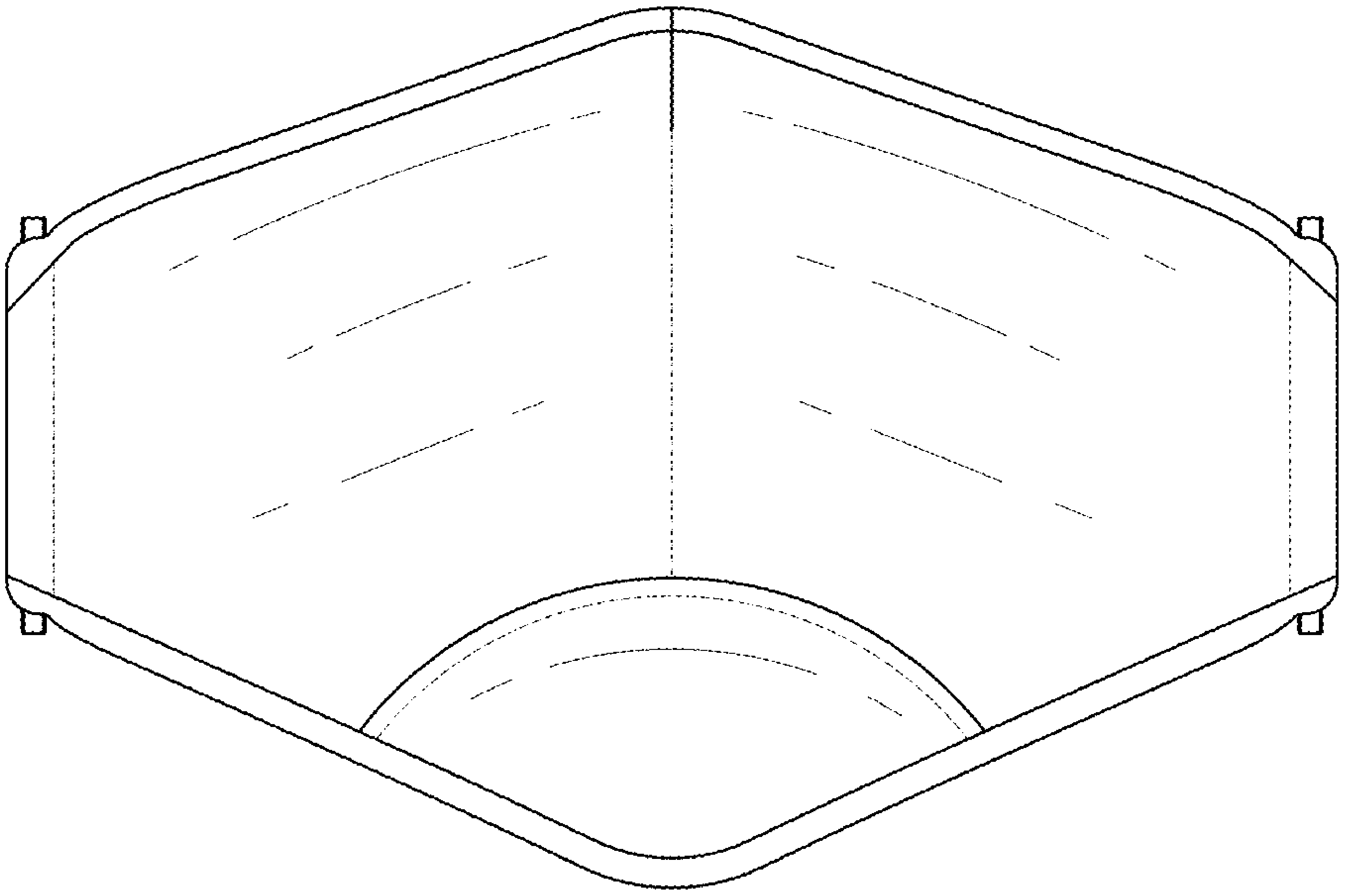

FIG. 2

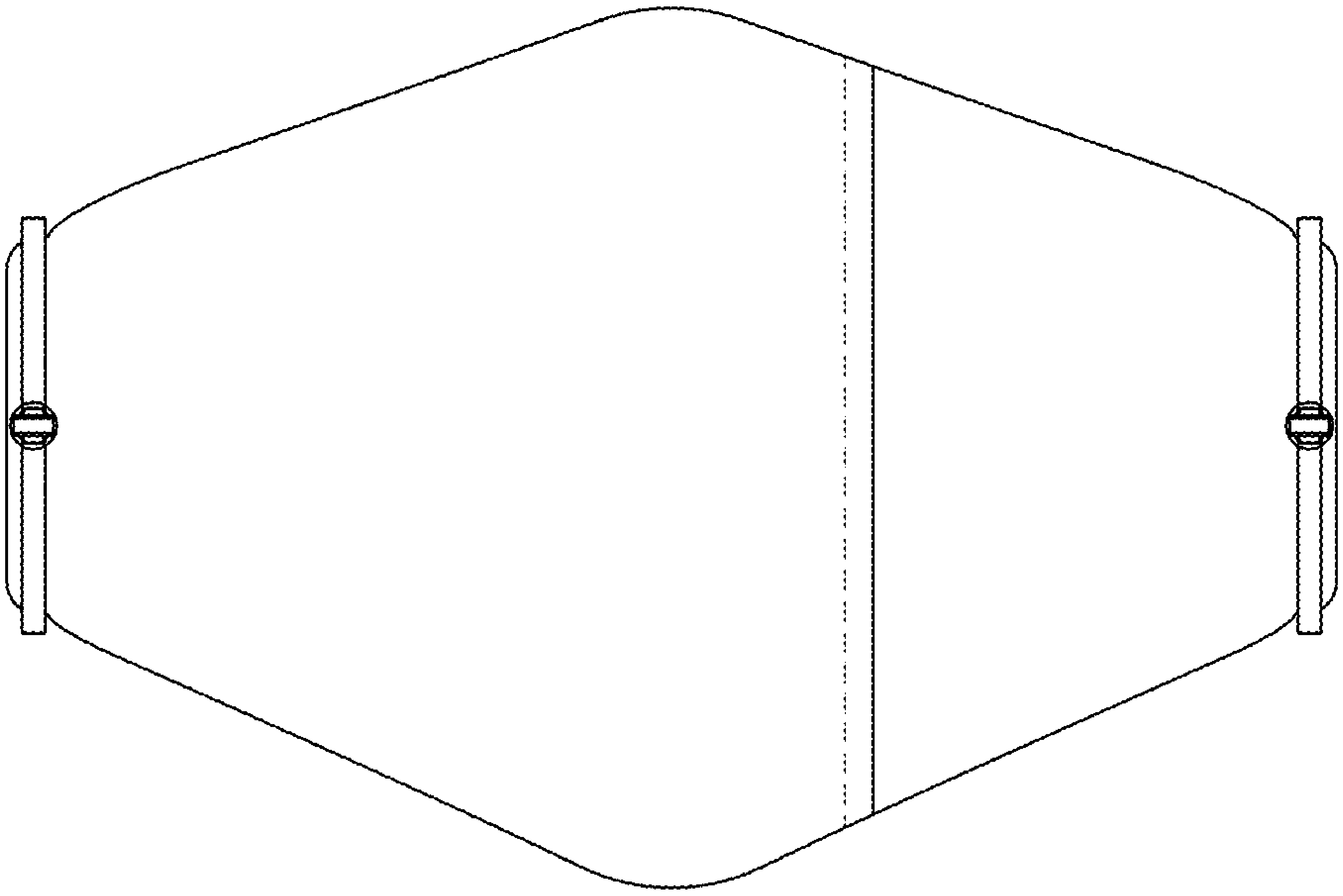

FIG. 3

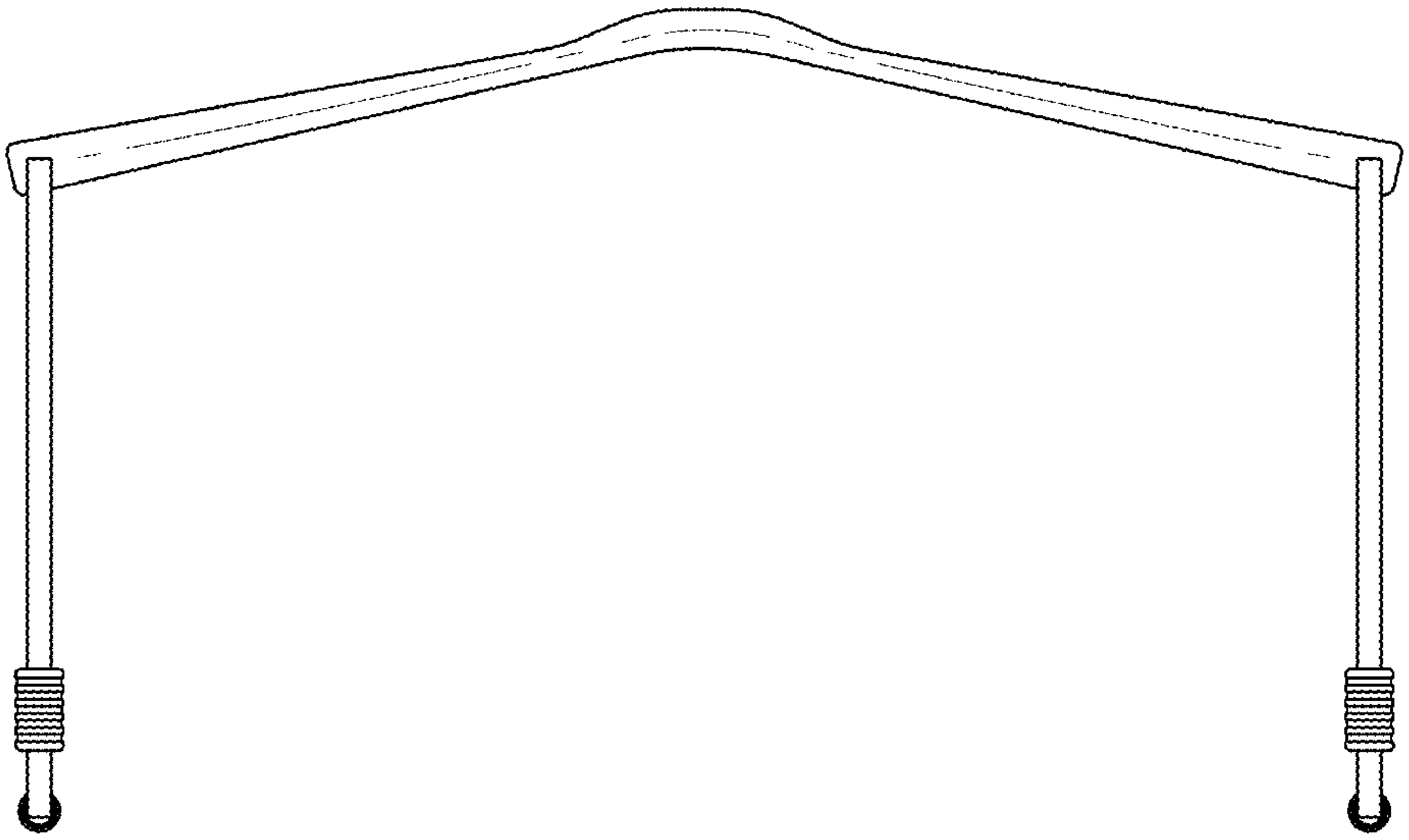

FIG. 4

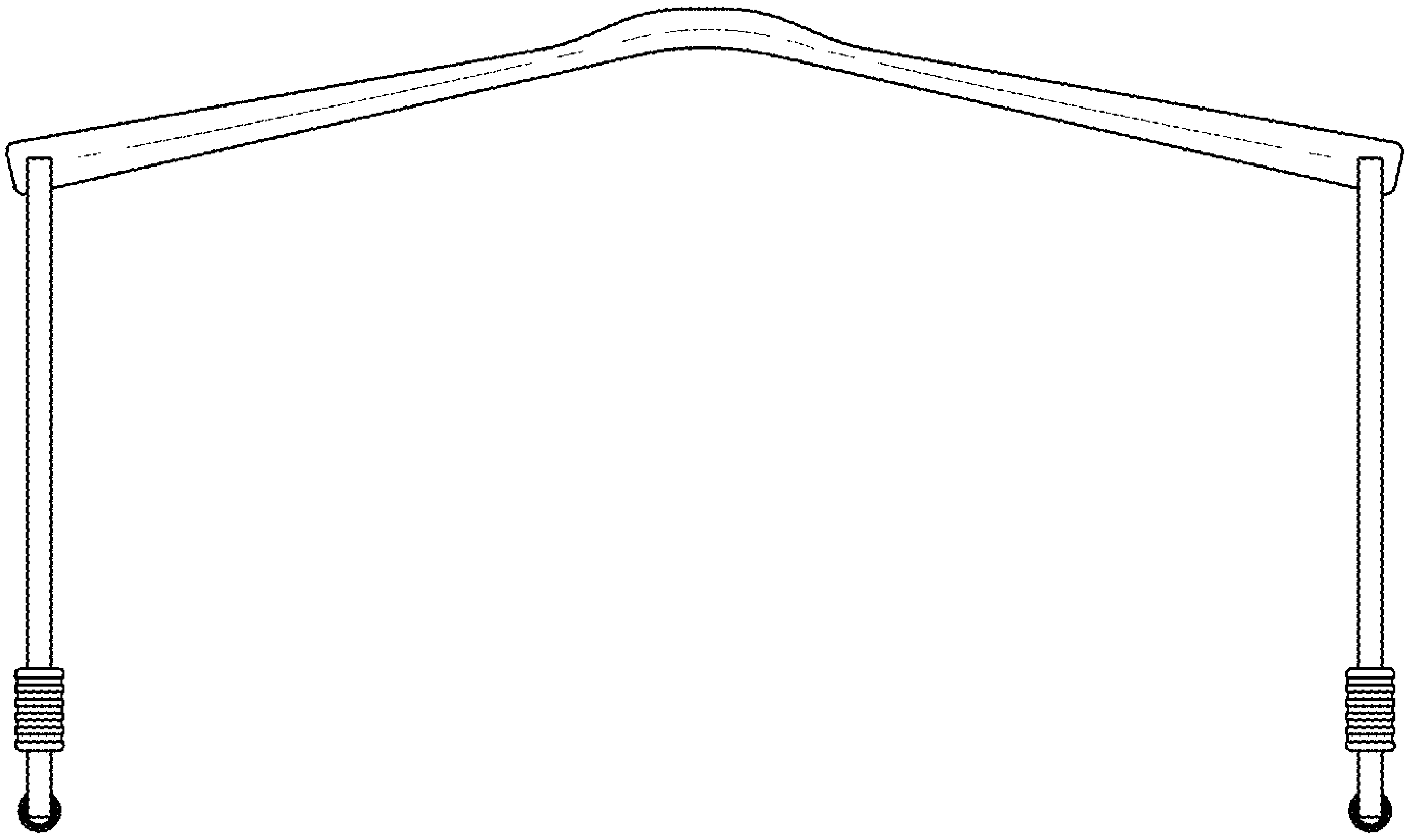

FIG. 5

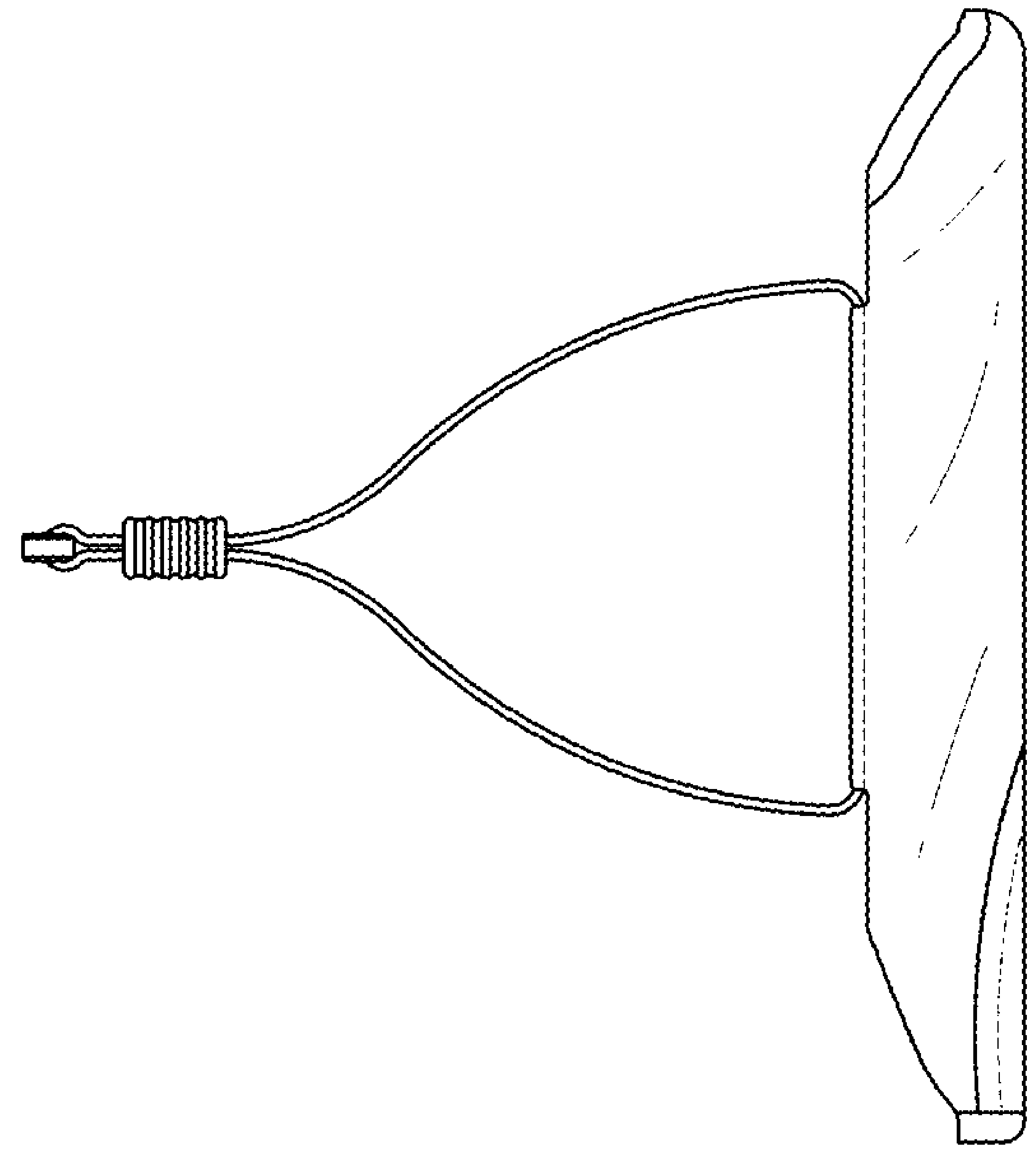

FIG. 6